TATENT COOPERATION TREAT



INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Artcle 36 and Rule 70)

Applicant's or agent's file reference IP-18852-PCT	FOR FURTHER ACT	CTION SeeNotificationofTransmittalofInternationalPreliminary Examination Report (Form PCT/IPEA/416)					
International application No.	International filing date(day/month/year)		Priority date (day/mont				
PCT/KR2003/000786	17 APRIL 2003 (17.		19 APRIL 2002 (19.04	1.2002)			
International Patent Classification (IPC) or national classification and IPC IPC7 C23C 16/455							
Applicant		•					
IPS LTD. et al							
This international preliminary examination report has been prepared by this International Preliminary Examining Authority and is transmitted to the applicant according to Article 36.							
2. This REPORT consists of a total of	2. This REPORT consists of a total of 3 sheets, including this cover sheet.						
This report is also accompanied by ANNEXES, i.e., sheets of the description, claims and/or drawings which have been amended and are the basis for this report and/or sheets containing rectifications made before this Authority (see Rule 70.16 and Section 607 of the Administrative Instructions under the PCT). These annexes consist of a total ofsheets.							
These affices consist of a total of	orsneets.						
3. This report contains indications relating to the following items: I X Basis of the report II Priority III Non-establishment of opinion with regard to novelty, inventive step and industrial applicability IV Lack of unity of invention V X Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement VI Certain documents cited VII Certain defects in the international application VIII Certain observations on the international application							
Date of submission of the demand	[Date of completion of t	his report				
23 APRIL 2003 (23.04.2003)		31 MAY 2004	(31.05.2004)				
Name and mailing address of the IPEA/I		Authorized officer		- III			
Korean Intellectual Property Office 920 Dunsan-dong, Seo-gu, Daejeon 302-701, Republic of Korea		CHO, Ji Hun					
Facsimile No. 82-42-472-7140	1	Celephone No. 82-42-	481-5528				

INTERNATIONAL PREI

NARY EXAMINATION REPORT

`	
International aplication No.	
/KR2003/000786	

I.	Basis	of the report				
1.	With	regard to the elements of the international application:*				
	\mathbf{x}	the international application as originally filed				
	X	the description:				
		pages 1-18 pages NONE	, as originally filed , filed with the demand			
		pages NONE , filed with the letter of	, med widi the demand			
	X	the claims:				
		pages 19-23 pages NONE , as amended (together with an	_ , as originally filed			
		pages NONE	~			
		pages NONE , filed with the letter of				
	X	the drawings:				
		pages 1-4 pages NONE	_ , as originally filed , filed with the demand			
		pages NONE, filed with the letter of	, med with the definant			
	X	the sequence listing part of the description:				
		1101 m	, as originally filed , filed with the demand			
		pages NONE , filed with the letter of	, mod with the definite			
2.	the i	regard to the language, all the elements marked above were available or furnished to this Auth nternational application was filed, unless otherwise indicated under this item. se elements were available or furnished to this Authority in the following language	ority in the language in which which is			
		the language of a translation furnished for the purposes of international search (under Rule 23	.1(b)).			
		the language of publication of the international application(under Rule 48.3(b)).				
		the language of the translation furnished for the purposes of international preliminary examination or 55.3).	ination(under Rules 55.2 and/			
3.		h regard to any nucleotide and/or amino acid sequence disclosed in the international appliminary examination was carried out on the basis of the sequence listing:	ication, the international			
		contained inthe international application in written form.				
		filed together with the international application in computer readable form.				
		furnished subsequently to this Authority in written form.				
		furnished subsequently to this Authority in computer readable form				
		The statement that the subsequently furnished written sequence listing does not go be international applicationas as filed has been furinshed.	yond the disc losure in the			
		The statement that the information recorded in computer readable form is identical to the written sequence listing has been furnished.				
4.	X	The amendments have resulted in the cancellation of:				
•	ليت	the description, pages NONE				
		X the claims, Nos. NONE				
		The drawings, sheet NONE				
5.						
		This report has been established as if (some of) the amendments had not been made, since go beyond the disclosure as filed, as indicated in the Supplemental Box(Rule 70.2(c)).**	they have been considered to			
*	in thi.	cement sheets which have been furnished to the receiving Office in response to an invitation un s opinion as "originally filed." and are not annexed to this report since they do not contain 0.17).	der Article 14 are referred to amendments (Rules 70.16			
**	Any r	eplacement sheet containing such amendments must be referred to under item I and annexed to) this report.			

V. Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

		<u>Y</u> ES
Clair	ns NONE	<u>N</u> O
S) Clain	ns 1-13	YES
Clair	ns NONE	NO
bility (IA) Clair	ns 1-13	YES
Clair	ms NONE	NO
	Clair Clair Clair bility (IA) Clair	Claims NONE Claims 1-13 Claims NONE billity (IA) Claims 1-13

2. Citations and explanations (Rule 70.7)

1. Reference is made to the following documents

D1: JP2-122825 (DENKIKAGAKUKOGYOKK) 10 March 1990 (1990-3-10)

D2: JP11-001773 (TOKYO ELECTRON LTD) 6 January 1773 (173-1-6)

D3: US5,567,243 (SONY CORP, MATERIAL RESEARCH CORP) 22 October 1996 (1996-10-22)

D4: JP4-293775 (FUJITSU LTD) 19 October 1992 (1992-10-19)

D5: JP4-136165 (SHIMADZU CORP) 11 MAY 1992 (1992-5-11)

- 2. The present application relates to an atomic film deposition (ALD) apparatus and ADL method for depositing a thin film on a wafer such as a semiconductor substrate using remote plasma. The present inventionis industrially applicavel in deposition of atomic fim.
- 3. D1 to D5 refer to atomic film deposition (ALD) apparatus. Among the components of the present invention, reaction chamber, reactive gas supply unit, reactive gas transfer line, and bypass line can be found in the referred documents. But, none of them discloses the combination of first bypass line and second bypass line that connect the first reactive gas supply and the reactive gas and radical supply unit to exhaust line, respectively.

They are thus not considered to be of a particular relevance in respect to the present application.

4. The presently claimed subject-matter is thus believed to be noble and to involve an inventive step when compared with the prior art as cited in the international Search Report (article 33(2) and (3) PCT).